

Supplementary Information

Energy-Distinguishable Bipolar UV Photoelectron Injection from LiCl-Promoted FAPbCl₃ Perovskite Nanorods

Jue Gong^a, Xun Li^a, Peijun Guo^b, Ian Zhang^a, Wei Huang^{c,d}, Ke Lu^a, Yingwen Cheng^a, Richard
D. Schaller^{b,c}, Tobin J. Marks^{c,d}, Tao Xu^{a,*}

^aDepartment of Chemistry and Biochemistry, Northern Illinois University, DeKalb, IL 60115
United States

^bCenter for Nanoscale Materials, Argonne National Laboratory, Argonne, IL 60439, United
States

^cDepartment of Chemistry, ^dMaterials Research Center, Northwestern University, 2145 Sheridan
Road, Evanston, IL 60208, United States

* Corresponding author

Prof. Tao Xu (Email: txu@niu.edu)

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Methods

Chemicals and precursor

Hydrochloric acid (HCl, 37.0%) and ethyl ether (anhydrous) were purchased from Fisher Chemical. Lead(II) chloride (PbCl₂, 99.999%), formamidinium acetate salt (HC(NH₂)NH₂·HCOOCH₃, 99%), 2-propanol (anhydrous, 99.5%) and dimethyl sulfoxide (DMSO, anhydrous, 99.9+%) were purchased from Aldrich. All chemicals were used as received without purification. HC(NH₂)₂Cl (FACl) was synthesized by reacting 1.1:1 molar ratio of HCl and

HC(NH₂)NH·HCOOCH₃ in a 100-mL round bottom flask immersed in ice bath, as followed by rotary evaporation at 60 °C to dry off the solvent. As-formed solid was then washed with copious amount of ethyl ether and accompanied with vacuum filtration. Finally, pure FAPbCl₃ product was obtained by drying in a vacuum oven at 60 °C overnight.

Synthesis of FAPbCl₃ and LiCl:FAPbCl₃ nanorods

The growth of FAPbCl₃ and LiCl:FAPbCl₃ nanostructures followed the methods reported in literatures^{1,2} with adaptations. In detail, 100 mg/mL PbCl₂/DMSO solution was first spun-coated on acetone-cleaned FTO glass (Pilkington Glass) at 1000 rpm for 10 seconds. The as-formed wet film was then quickly transferred to a 50-mL ethyl ether bath for 5 minutes. Crystallized PbCl₂ film was then annealed on a hot plate at 100 °C for about 30 minutes, before being dipped into 10 mg/mL FAPbCl₃ or 10 mg/mL FAPbCl₃ & 1 mg/mL LiCl in 2-propanol solutions (with lead precursor coated sides facing down) for respectively synthesizing pristine FAPbCl₃ or LiCl:FAPbCl₃ nanorods for 24 hours.

Perovskite UV photodetectors

Gold layers were deposited on the as-prepared perovskite/FTO substrates with a thermal evaporator (Edward 306 A) to finish construction of the UV photodetectors. 365-nm UVL-4F UV lamp was utilized to generate photocurrents without magnitude oscillation, while UVGL-25 Multiband UV lamp with 254/365 nm wavelengths was used to generate photocurrents with damping magnitudes. Photocurrents were collected under chronoamperometry on a CH Instrument potentiostat under sample period of 0.001 s or 0.01 s, with equilibration time of 5 s and zero voltage bias. Potentiostatic electrochemical impedance spectroscopy was performed on a Gamry Reference 600 potentiostat to measure Nyquist plots of LiCl:FAPbCl₃ photodetector, under

parameters of 10-s initial delay, 100000-Hz initial frequency, 0.001-Hz final frequency, 10 points/decade, AC voltage of 5 mV·rms and zero DC voltage vs. open-circuit voltage.

Structural, morphological and optical characterizations

X-ray diffraction patterns of perovskite nanostructured films were collected from 10-50° of 2 θ using a Bruker D2 Phaser Diffractometer with a sampling speed of 0.1°/s. Microscopic images of synthesized perovskite nanorods were taken with a scanning electron microscope (TESCAN, Vega II SBH) under 5.21-kx magnification. Optical reflectance was performed with a Filmetrics F20-EXR thin-film analyzer, with spectral range of 380 to 1700 nm. Fluorescence was measured with a Hitachi F-2500 fluorescence spectrophotometer equipped with xenon lamp as light source, where a 350-nm excitation (2.5-nm slit width) was applied to collect emissions (2.5-nm slit width) of perovskite nanostructured films with a scan speed of 15 nm/minute from 350 to 550 nm spectral range.

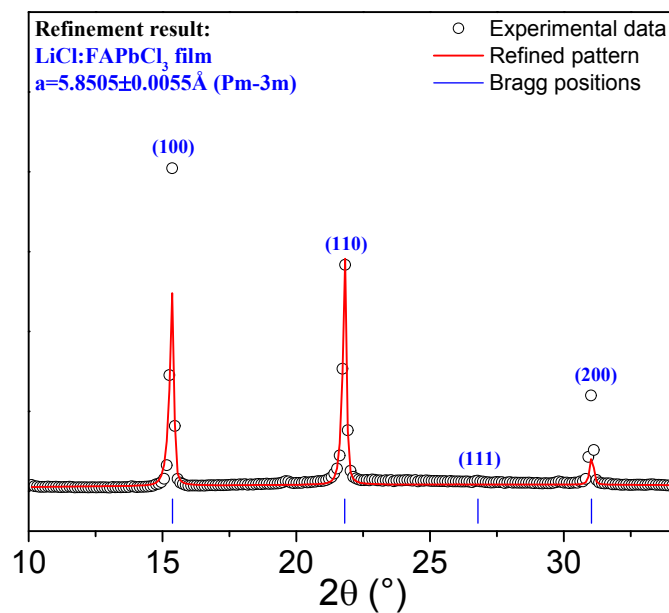


Fig. S1 XRD refinement of LiCl:FAPbCl₃ nanostructured film against reported cubic FAPbCl₃ (Pm-3m)³, with a refined cell parameter being $5.8505\pm0.0055\text{\AA}$.

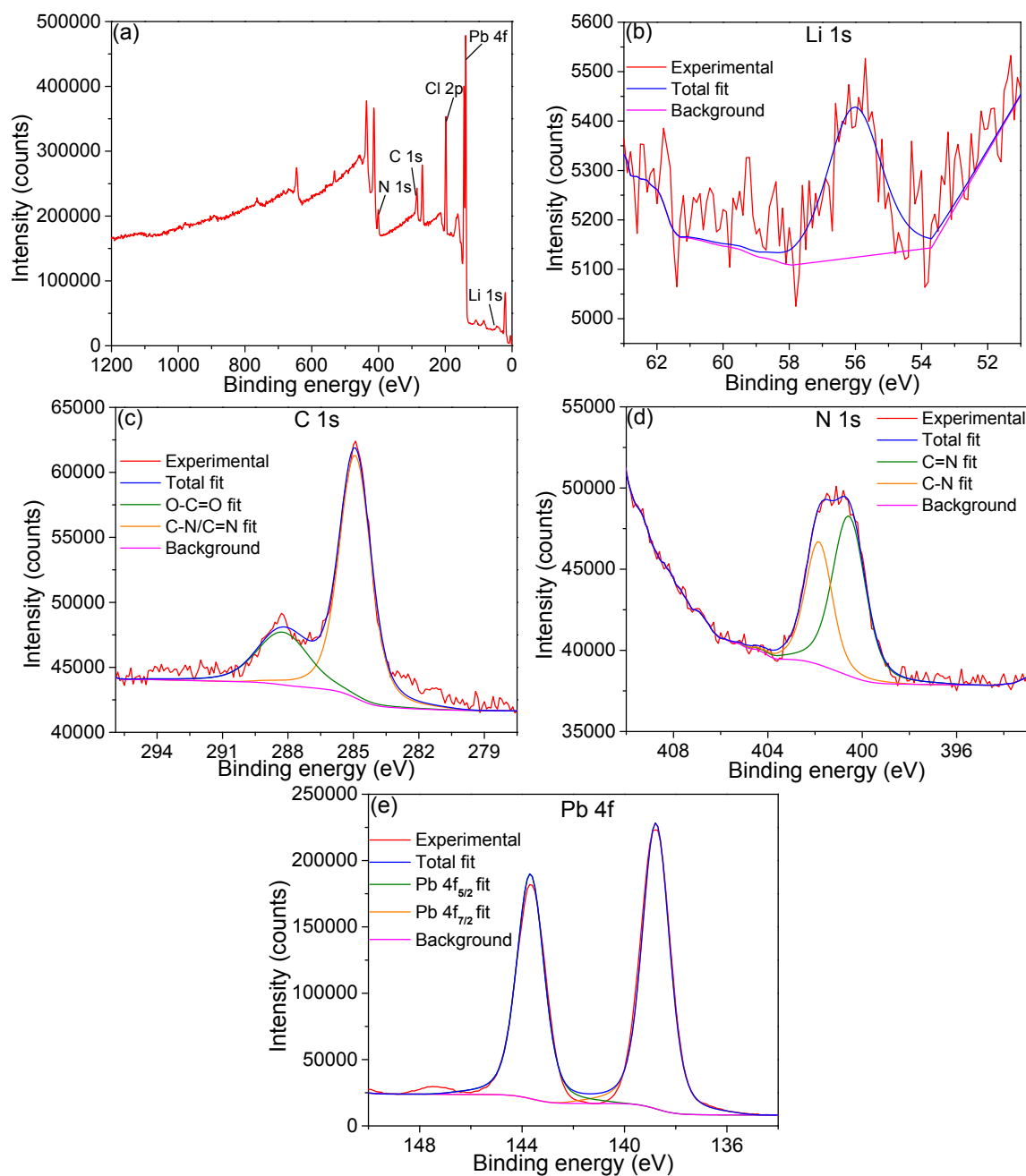


Fig. S2 X-ray photoelectron spectra of LiCl:FAPbCl₃ nanostructured film. (a) Survey scan of LiCl:FAPbCl₃ sample. Resolution scans of (b) Li 1s, (c) C 1s, (d) N 1s and (e) Pb 4f electrons.

Table S1. Calculated atomic compositions of scanned elements from XPS measurements of LiCl:FAPbCl₃ nanostructured film.

Name	Binding energy (eV)	FWHM (eV)	Area (CPS·eV)	Atomic (%)
C1s Scan A	283.90	1.78	35905.47	0.00
C1s Scan B	287.16	2.81	14039.63	0.00
C1s Combined	0.00	0.00	49945.10	53.70
Li1s Scan A	55.03	1.85	609.94	9.97
Pb4f 7/2 Scan A	137.78	1.36	307474.25	16.41
Pb4f 5/2 Scan A	142.68	1.36	241776.69	0.00
N1s Scan A	400.86	1.45	11945.82	0.00
N1s Scan B	399.54	1.69	17740.83	0.00
N1s Combined	0.00	0.00	29686.65	19.92

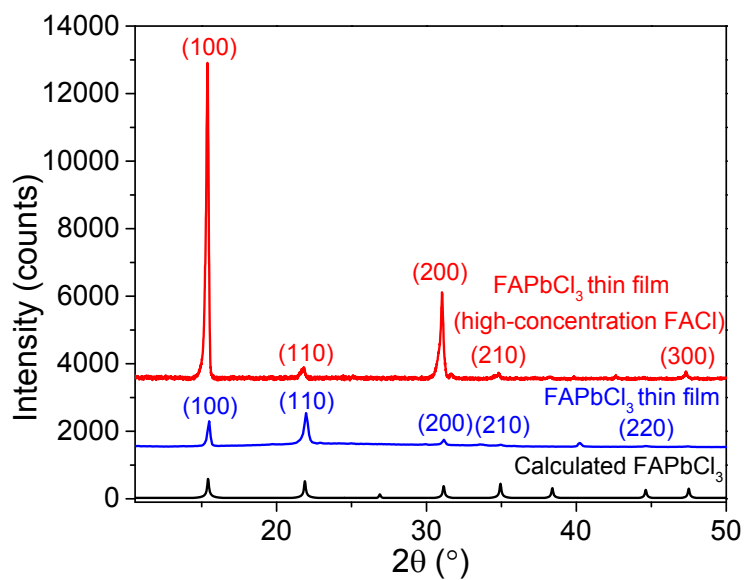


Fig. S3 Comparison of XRD pattern of high-concentration FAPbCl₃ (red) with low-concentration FAPbCl₃ (blue, Fig. 1a), and calculated FAPbCl₃ reference³ (black).

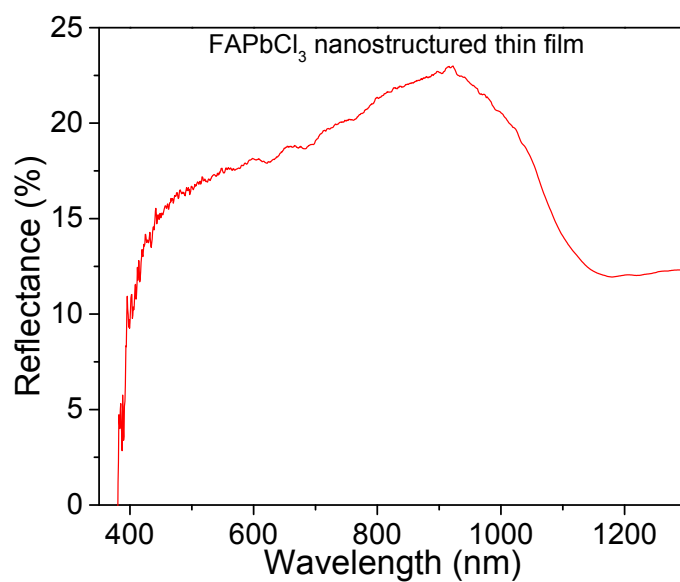


Fig. S4 Optical reflectance spectrum of FAPbCl₃ nanostructured thin film.

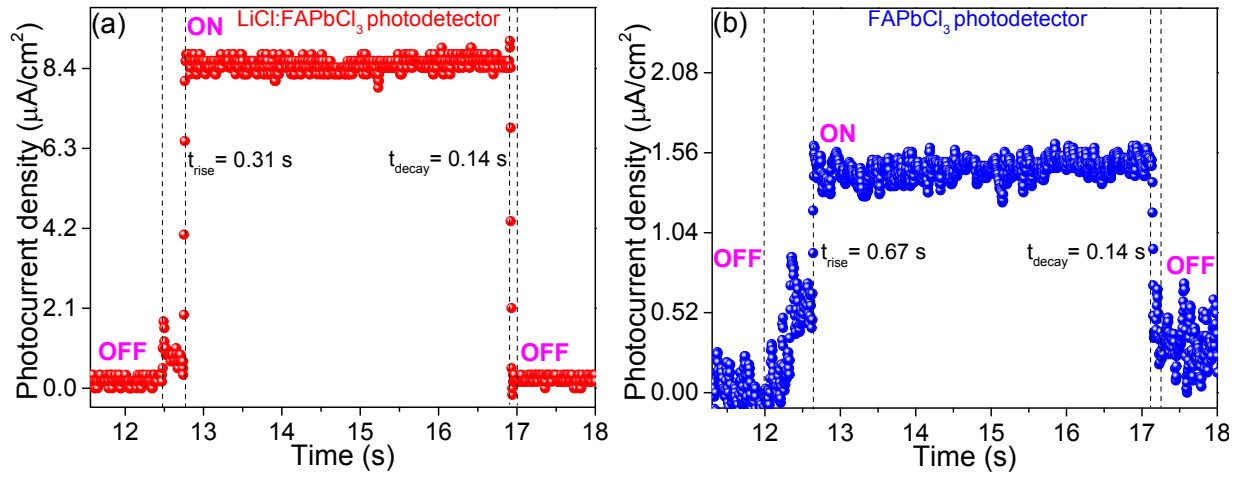


Fig. S5 Rise and decay kinetics of photocurrents on LiCl:FAPbCl₃ (a) and FAPbCl₃ (b) UV photodetectors.

Table S2. Summary of materials applied in UV photodetectors with corresponding performance parameters.

Material	Wavelength (nm)	Responsitivity	Rise time	Decay time	Reference
ZnO thin film	380	0.1 mA/W	48 s	0.9 s	4, 5
ZnO nanocrystal	370	61 A/W	0.1 s	1 s	6, 7
ZnO-SnO ₂ nanofibers	300	/	32.2 s	7.8 s	6, 8
GaN film	325	340 mA/W	0.28 s	0.45 s	6, 9
NiO film	365	4.5 A/W	0.266 s	0.2 s	6, 10
TiO ₂ thin film	260	199 A/W	6 s	15 s	4, 11
SrTiO ₃ single crystal	330	213 mA/W	1.3 ns	/	4, 12
LaAlO ₃ single crystal	200	71.8 mA/W	/	/	4, 13
LiNbO ₃ single crystal	300	17.1 mA/W	0.5 ns	/	4, 14
LiTaO ₃ single crystal	235	2 mA/W	0.2 ns	/	4, 15
ZnO/SrTiO ₃ heterostructure	365	/	/	/	4, 16
TbMnO ₃ /Nb-SrTiO ₃ heterostructure	365	/	510 ns	/	4, 17
MAPbCl ₃ single crystal	365	46.9 mA/W	24 ms	62 ms	4
MAPbCl ₃ single crystal	255	450 mA/W	15 ms	55 ms	18
MAPbBr ₃ single crystal	255	300 mA/W	2.5 ms	2.5 ms	18
MAPbI ₃ single crystal	255	120 mA/W	2 ms	2 ms	18
MAPbCl ₃ thin film	360	7.56 A/W	170 μ s	220 μ s	19
CsPbCl ₃ nanocrystal thin film	365	1.89 A/W	41 ms	43 ms	6
FAPbCl₃ nanorod film	365	29 mA/W	0.67 s	0.14 s	This work
LiCl:FAPbCl₃ nanorod film	365	167 mA/W	0.31 s	0.14 s	This work

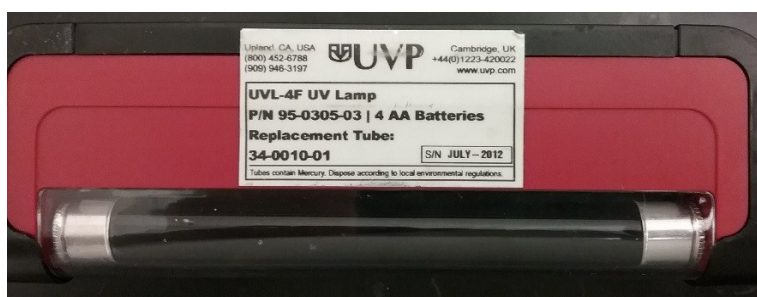


Fig. S6 Picture of the DC-powered UV lamp, which operates on constant current from 4 AA batteries.

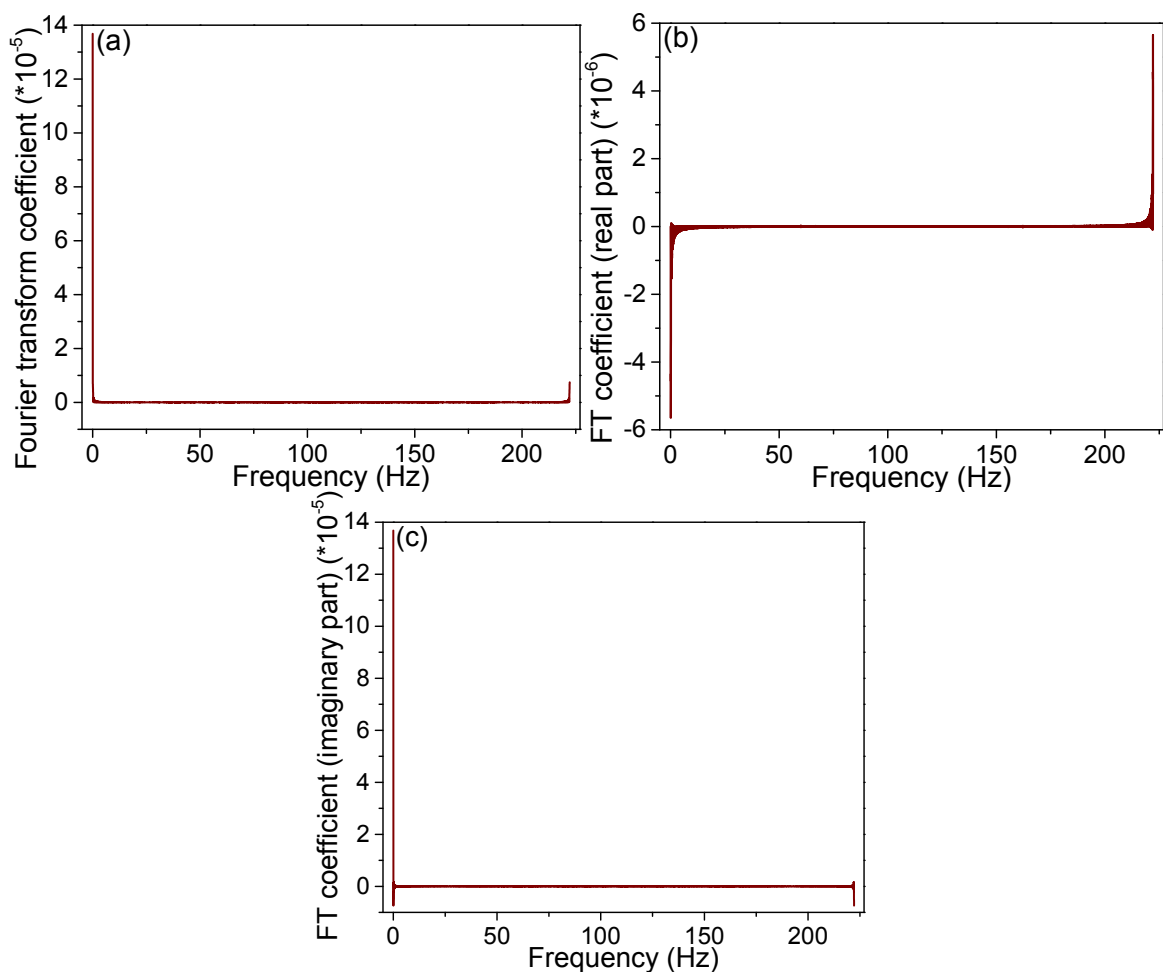


Fig. S7 Fourier transform of transient photocurrents of LiCl:FAPbCl₃ nanorod film shown in Figure 2a. (a) Fourier transform coefficient plot. (b) Real-part Fourier transform coefficient plot. (c) Imaginary-part Fourier transform coefficient plot.

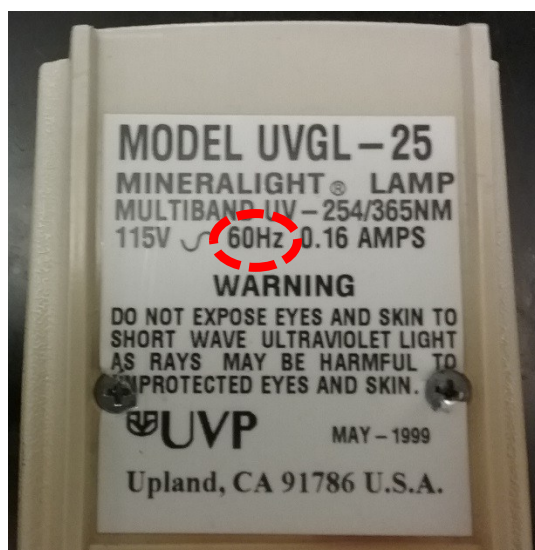


Fig. S8 Picture of the AC-powered UV lamp, which operates on 60-Hz oscillating current.

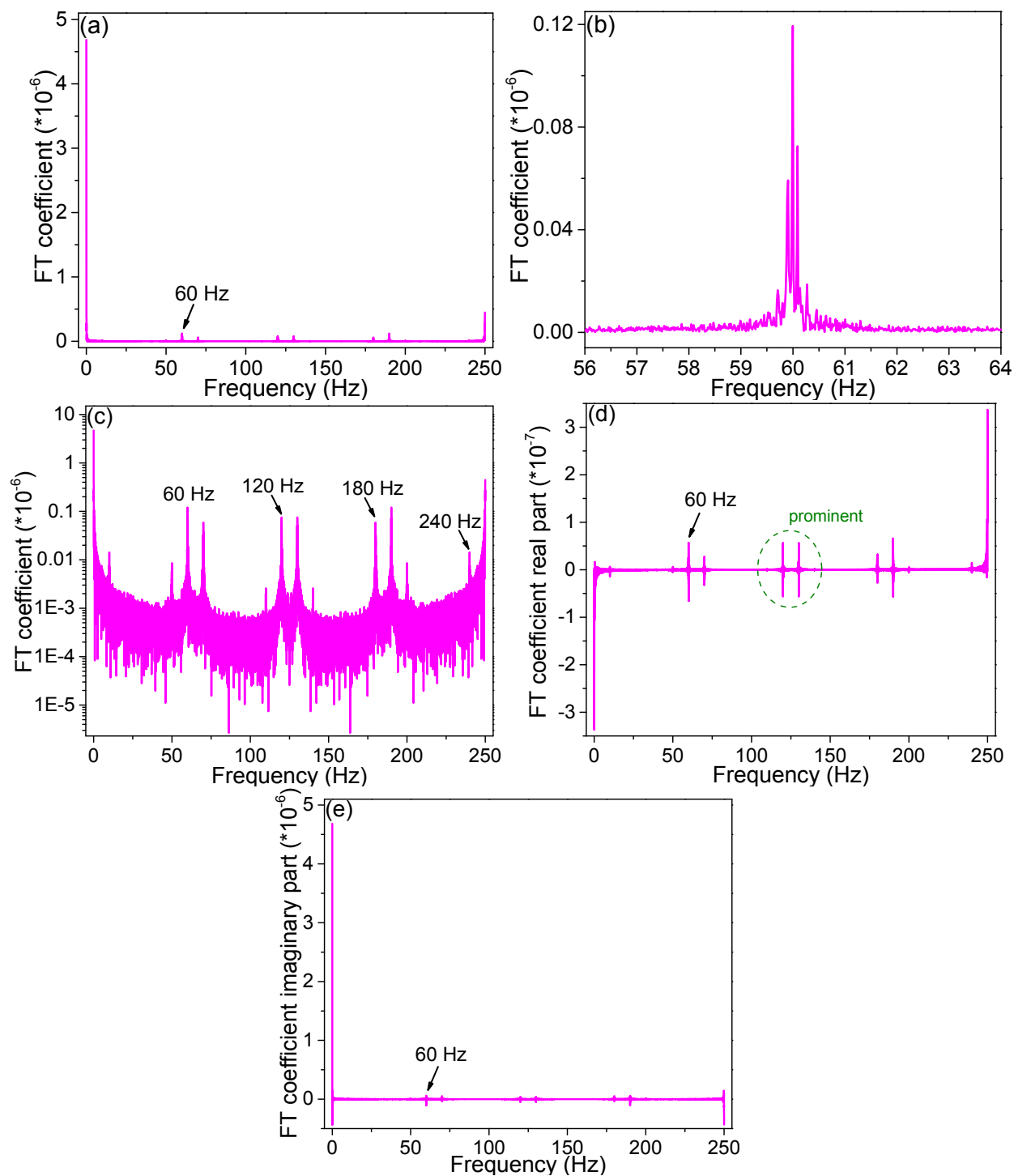


Fig. S9 Fourier transform of on-off photocurrents of LiCl:FAPbCl₃ nanostructured film achieved under 365-nm AC-powered UV illumination. (a) Fourier transform coefficient plot. (b) Zoomed-in view of the coefficient plot in the range of 56 to 64 Hz. (c) Logarithmic scale of coefficient plot. (d) and (e) Real-part and imaginary-part coefficient plots, respectively.

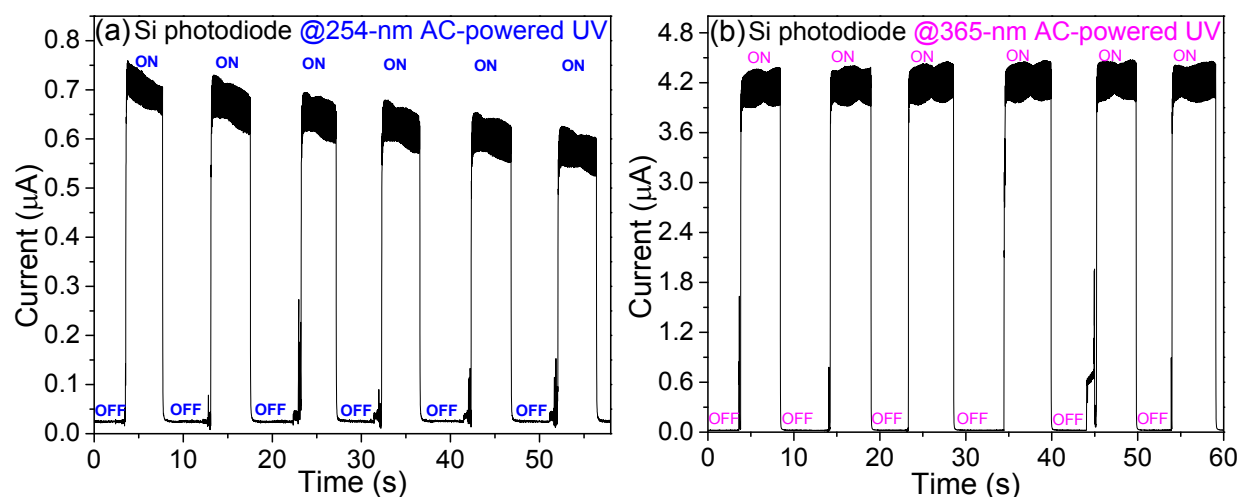


Fig. S10 On-off photocurrents of Si photodiode under 254-nm (a) and 365-nm (b) AC-powered UV illuminations with sampling period of 0.01 s.

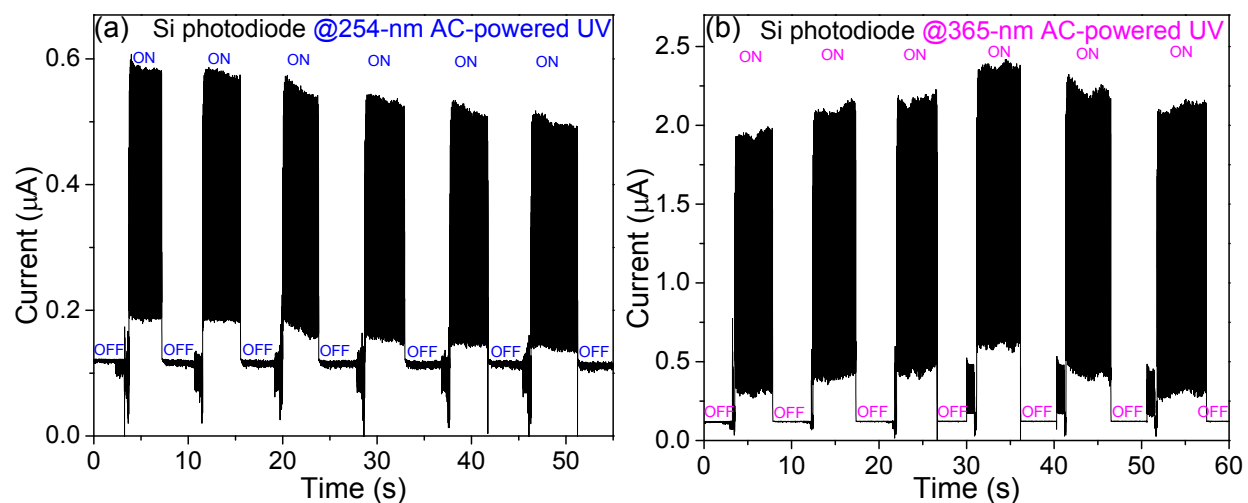


Fig. S11 On-off photocurrents of Si photodiode under 254-nm (a) and 365-nm (b) AC-powered UV illuminations with sampling period of 0.001 s.

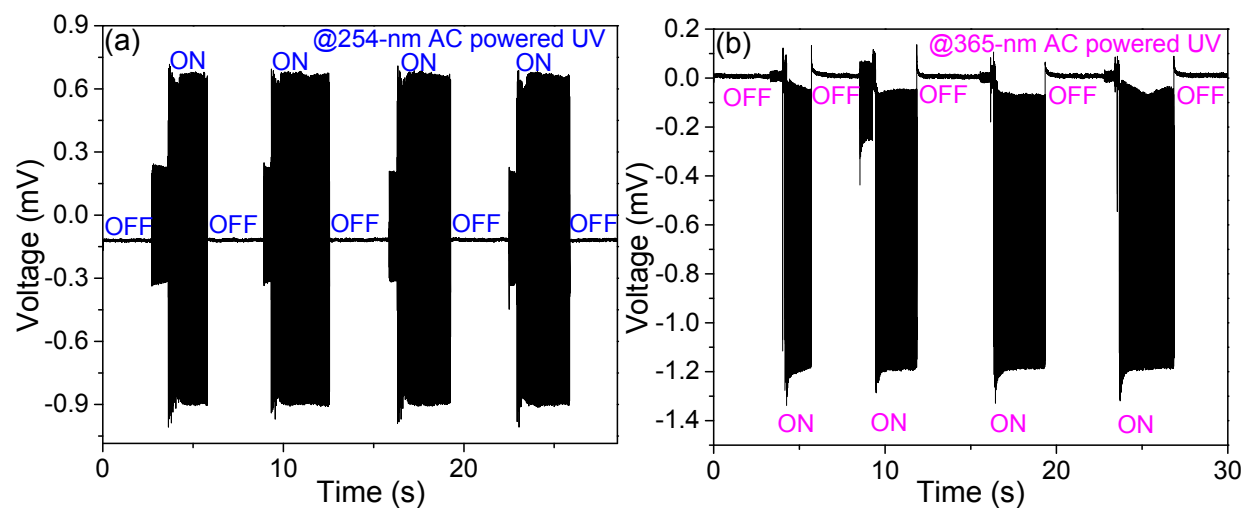


Fig. S12 On-off photovoltages of LiCl:FAPbCl₃-based photodetector under 254-nm (a) and 365-nm (b) AC-powered UV illuminations.

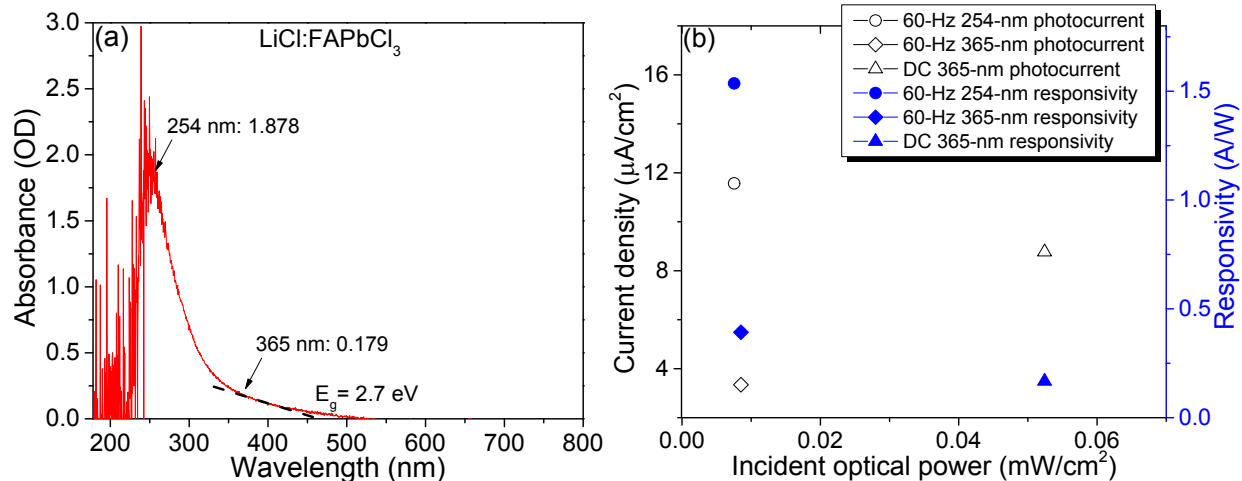


Fig. S13 UV-Vis absorbance spectrum of LiCl:FAPbCl₃ nanostructured film, which shows an absorption onset at around 460 nm (a), and summary of photocurrent densities (left y-axis) with corresponding responsivities (right y-axis) of LiCl:FAPbCl₃ (b).

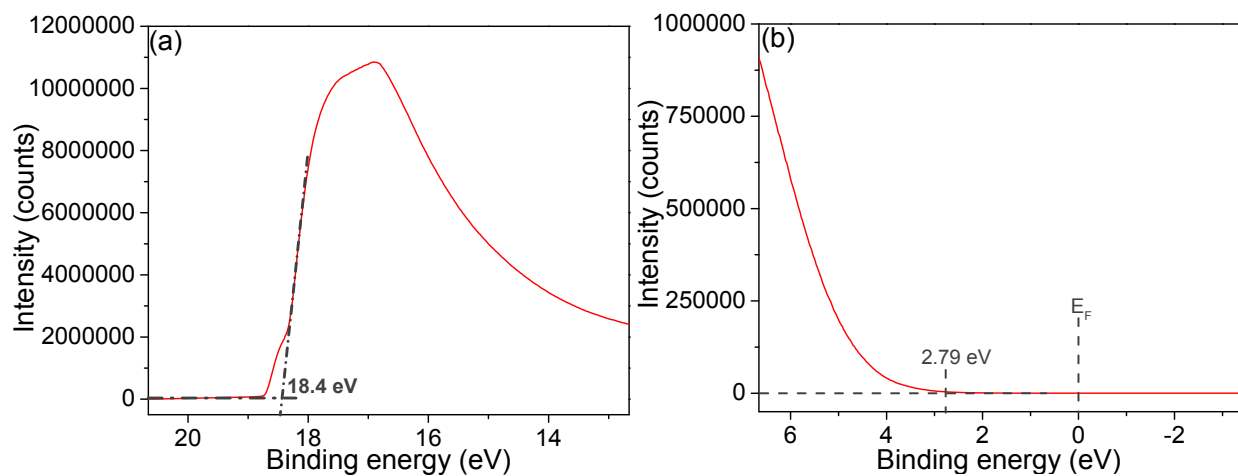


Fig. S14 Ultraviolet photoelectron spectra (UPS) of LiCl:FAPbCl₃ nanostructured film. UPS in the ranges of 12 - 20 eV (a), -3 - 6 eV (b) of electron binding energies. Based on the shown spectrum intersections with baseline (18.4 eV and 2.79 eV), the width of binding energy is determined as $\Delta E = 18.4 \text{ eV} - (2.79 \text{ eV}) = 15.6 \text{ eV}$, which leads to the valence band maximum of LiCl:FAPbCl₃ as: $15.6 \text{ eV} - 21.2 \text{ eV (He I UV photon)} = -5.6 \text{ eV}$.²⁰⁻²³

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